ABSTRACT OF THE DISCLOSURE

In a processing apparatus which performs a film deposition by alternately supplying a plurality of source gases, the source gases are prevented from reacting within an exhaust pipe so as to prevent the exhaust pipe from clogging due to a reaction by-product. A gas supply to a processing container is switched between a $TiCl_4$ supply system and a $NH_3$ supply system. Additionally, a gas exhaust from the processing container is switched between a $TiCl_4$ exhaust system and a $NH_3$ exhaust system. The gas exhaust is switched to the $TiCl_4$ exhaust system when the gas supply is switched to the $TiCl_4$ supply system, and the gas exhaust is switched to the $NH_3$ exhaust system when the gas supply is switched to the $NH_3$ supply system. The switching is performed by a stop valve provided to each of the supply system and the exhaust system.